

said oxidative gas at a pressure higher than that needed at a time of evacuating said trap mechanism and then exhausting said trapped oxidative gas plural times.

42. (New) The impurity-gas removing method according to claim 39, wherein said reaction by-product is a product produced as a cleaning gas reacts with a by-product of a film deposition gas.

43. (New) The impurity-gas removing method according to claim 39, wherein said process gas is one of a titanium-containing gas, tungsten-containing gas, tantalum-containing gas and silicon-containing gas.

44. (New) The impurity-gas removing method according to claim 39, wherein said oxidative gas is at least one of an oxygen-containing gas.

REMARKS

Favorable consideration of this application, as presently amended, is respectfully requested.

Claims 26-44 are pending in this application. Claims 26-33 are allowed.

The present Preliminary Amendment is submitted to present new Claims 34-44 for examination. New Claims 34-44 are deemed to be self-evident from the original disclosure, and thus are not deemed to raise any issues of new matter.

The present application is believed to be in condition for a further examination on the merits to new Claims 34-44. Favorable consideration of those claims is respectfully requested.

Respectfully submitted,

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IN THE CLAIMS

Claims 34-44 (New).